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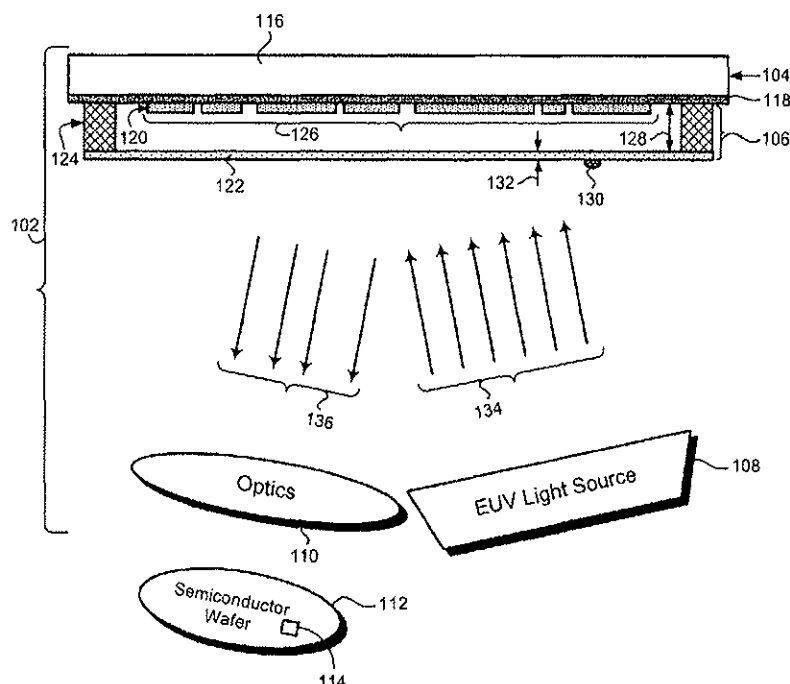
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(54) Title: **EUV PELLICLE WITH INCREASED EUV LIGHT TRANSMITTANCE**



(57) Abstract: According to one exemplary embodiment, an extreme ultraviolet (EUV) pellicle (106) for protecting a lithographic mask (104) includes an aerogel film (122). The pellicle further includes a frame (124) for mounting the aerogel film over the lithographic mask. The aerogel film causes the pellicle to have increased EUV light transmittance.